



## *EE141-Spring 2010 Digital Integrated Circuits*

### Lecture 20 Technology Scaling

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1

### *Administrativa*

- ❑ Midterm 2 on We April 7 6:30-8pm in 277 Cory
  - Open book.
  - Covers everything until Lecture 17 (DOMINO LOGIC). Registers and timing NOT included.
- ❑ Review Session: Tu April 6 6:30-8pm in 289 Cory
- ❑ DO NOT FORGET THE PROJECT!
  - Extra office hours of TAs on Mo and Tu (during lab hours) in 353 Cory
- ❑ Project Phase 1 has been graded. Results will be posted early next week.

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2

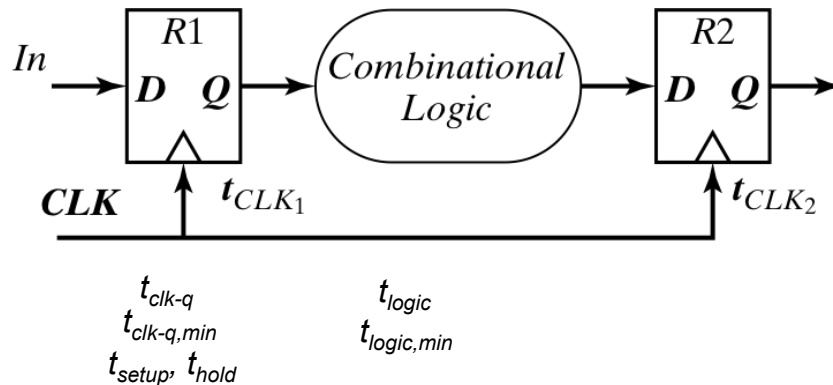
## *Class Material*

- Last lecture
  - Timing
- Today's lecture
  - Technology Scaling
- Reading (Ch 5)



## *Timing*

## Timing Constraints



Cycle time (max):  $T_{CLK} > t_{clk-q} + t_{logic} + t_{setup}$

Race margin (min):  $t_{hold} < t_{clk-q,min} + t_{logic,min}$

## Clock Constraints in Edge-Triggered Systems

If launching edge is late and receiving edge is early, the data will not be too late if:

$$t_{clk-q} + t_{logic} + t_{setup} < T_{CLK} - t_{JS,1} - t_{JS,2} + \delta$$

Minimum cycle time is determined by the maximum delays through the logic

$$t_{clk-q} + t_{logic} + t_{setup} - \delta + 2t_{JS} < T_{CLK}$$

Skew can be either positive or negative

## Clock Constraints in Edge-Triggered Systems

If launching edge is early and receiving edge is late:

$$t_{clk-q,min} + t_{logic,min} - t_{JS,1} > t_{hold} + t_{JS,2} + \delta$$

Minimum logic delay

$$t_{clk-q,min} + t_{logic,min} > t_{hold} + 2t_{JS} + \delta$$

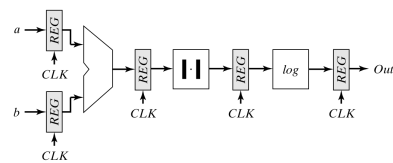
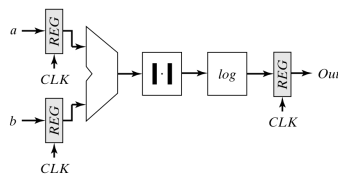
(This assumes jitter at launching and receiving clocks are independent – which usually is not true)

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7

## Pipelining



Reference

Clock Period	Adder	Absolute Value	Logarithm
1	$a_1 + b_1$		
2	$a_2 + b_2$	$ a_1 + b_1 $	
3	$a_3 + b_3$	$ a_2 + b_2 $	$\log( a_1 + b_1 )$
4	$a_4 + b_4$	$ a_3 + b_3 $	$\log( a_2 + b_2 )$
5	$a_5 + b_5$	$ a_4 + b_4 $	$\log( a_3 + b_3 )$

Pipelined

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8

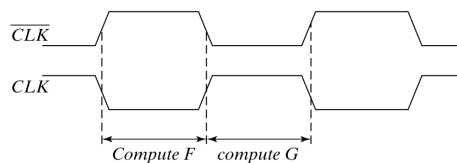
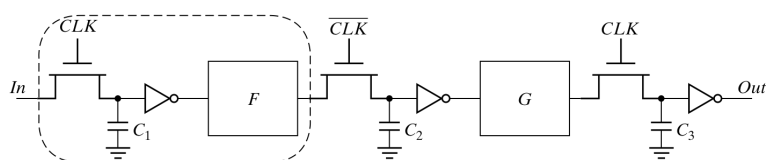
## Loop Unrolling

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9

## Latch-Based Clocking



(Domino logic almost always uses latch-based clocking)

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## Latch vs. Flip-flop

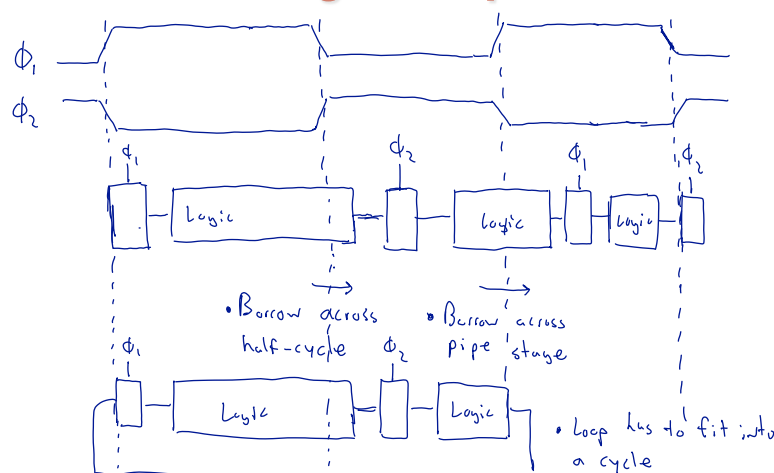
- In a flip-flop based system:
  - Data launches on one rising edge
    - And must arrive before next rising edge
  - If data arrives late, system fails
    - If it arrives early, wasting time
  - Flip-flops have hard edges
- In a latch-based system:
  - Data can pass through latch while it is transparent
  - Long cycle of logic can borrow time into next cycle
    - As long as each loop finished in one cycle

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## Time Borrowing Example



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12

## *Latch vs. Flip-flop Summary*

- Flip-flops generally easier to use
  - Most digital ASICs designed with register-based timing
- But, latches (both pulsed and level-sensitive) allow more flexibility
  - And hence can potentially achieve higher performance
  - Latches can also be made more tolerant of clock un-certainty
  - More in EE241

## *CMOS Transistor Scaling*



## Goals of Technology Scaling

- ❑ Make things cheaper:
  - Want to sell more functions (transistors) per chip for the same money
  - Or build same products cheaper
  - Price of a transistor has to be reduced
- ❑ But also want to be faster, smaller, lower power...

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15

## Technology Scaling

- ❑ Benefits of 30% “Dennard” scaling (1974):
  - Double transistor density
  - Reduce gate delay by 30% (increase operating frequency by 43%)
  - Reduce energy per transition by 65% (50% power savings @ 43% increase in frequency)
- ❑ Die size used to increase by 14% per generation (not any more)
- ❑ Technology generation spans 2-3 years

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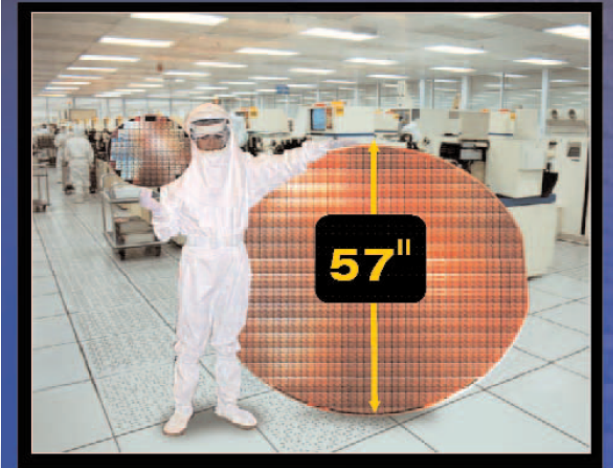
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16



## *Moore was not always accurate*

### **Projected 2000 Wafer, circa 1975**

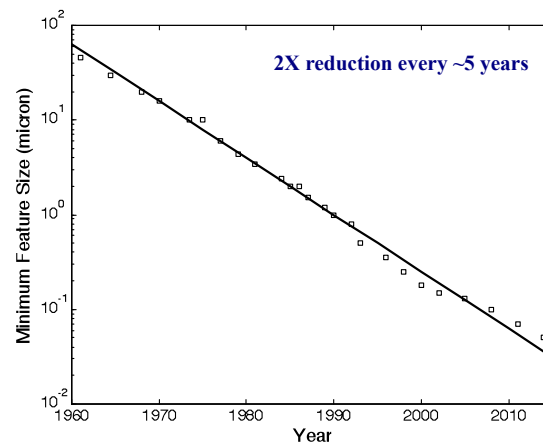


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17

## *Technology Scaling (1)*

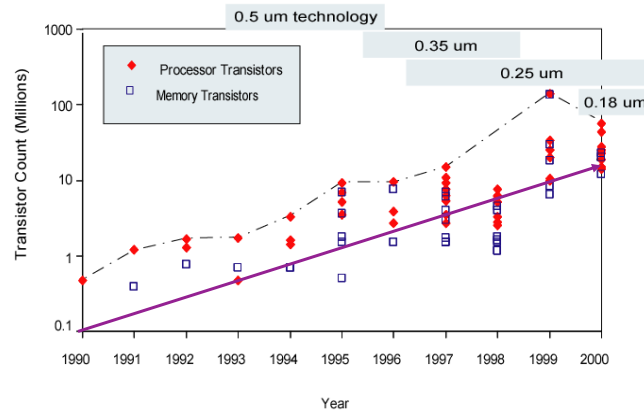
**Minimum Feature Size**

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18

## Technology Scaling (2)



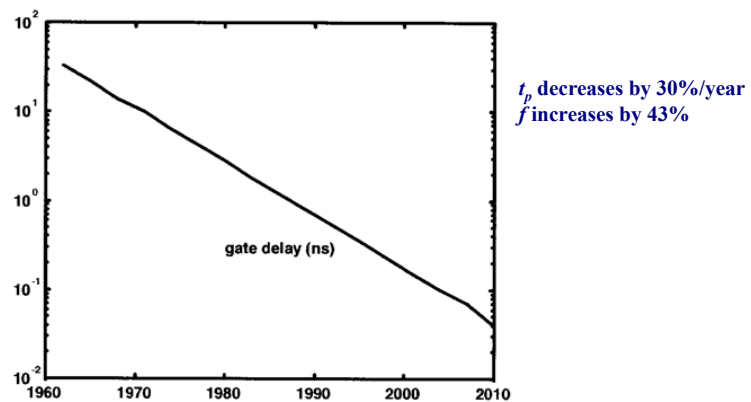
**Number of components per chip**

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19

## Technology Scaling (3)



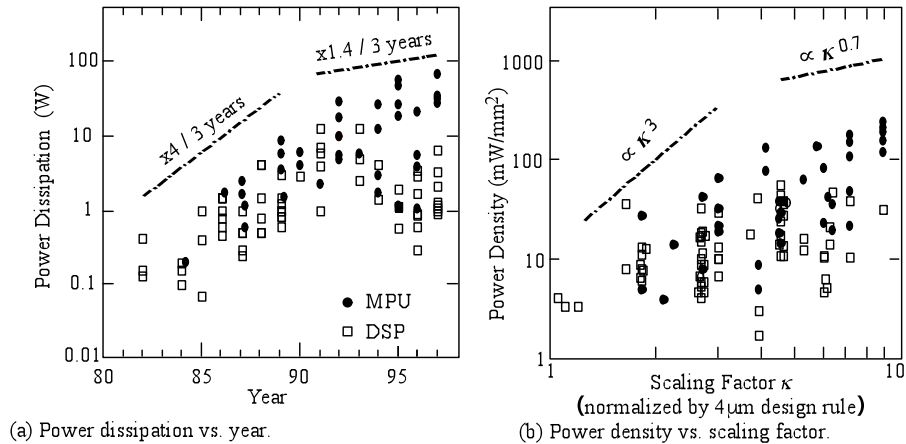
**Propagation Delay**

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## Technology Scaling (4)



From Kuroda

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## Technology Scaling Models

- **Full Scaling (Constant Electrical Field)**

ideal model — dimensions and voltages scale together by the same factor  $S$

- **Fixed Voltage Scaling**

most common model until 1990's  
only dimensions scale, voltages remain constant

- **General Scaling**

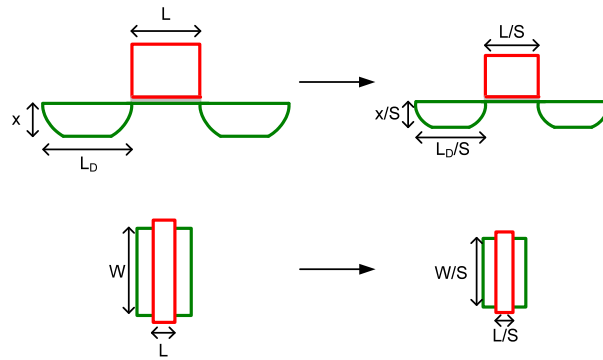
most realistic for today's situation —  
voltages and dimensions scale with different factors

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## Scaling



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## Full Scaling (Dennard, Long-Channel)

- $W, L, t_{ox}$ :  $1/S$
- $V_{DD}, V_T$ :  $1/S$
- Area:  $WL$
- $C_{ox}$ :  $1/tox$
- $C_L$ :  $C_{ox}WL$
- $I_D$ :  $C_{ox}(W/L)(V_{DD}-V_T)^2$
- $R_{eq}$ :  $V_{DD}/I_{DSAT}$

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24

## Full Scaling (Dennard, Long-Channel)

- $W, L, t_{ox}: 1/S$
- $V_{DD}, V_T: 1/S$
- $t_p: R_{eq} C_L$
- $P_{avg}: C_L V_{DD}^2 / t_p$
- $P_{avg}/A: C_{ox} V_{DD}^2 / t_p$

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## Scaling Relationships for Long Channel Devices

Parameter	Relation	Full Scaling	General Scaling	Fixed Voltage Scaling
$W, L, t_{ox}$		$1/S$	$1/S$	$1/S$
$V_{DD}, V_T$		$1/S$	$1/U$	1
$N_{SUB}$	$V/W_{depl}^2$	$S$	$S^2/U$	$S^2$
Area/Device	$WL$	$1/S^2$	$1/S^2$	$1/S^2$
$C_{ox}$	$1/t_{ox}$	$S$	$S$	$S$
$C_L$	$C_{ox}WL$	$1/S$	$1/S$	$1/S$
$k_n, k_p$	$C_{ox}W/L$	$S$	$S$	$S$
$I_{av}$	$k_{n,p} V^2$	$1/S$	$S/U^2$	$S$
$t_p$ (intrinsic)	$C_L V / I_{av}$	$1/S$	$U/S^2$	$1/S^2$
$P_{av}$	$C_L V^2 / t_p$	$1/S^2$	$S/U^3$	$S$
PDP	$C_L V^2$	$1/S^3$	$1/SU^2$	$1/S$

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26

## *Full Scaling (Dennard, Short-Channel)*

- $W, L, t_{ox}: 1/S$
- $V_{DD}, V_T: 1/S$
- Area:  $WL$
- $C_{ox}: 1/t_{ox}$
- $C_L: C_{ox}WL$
- $I_D: WC_{ox}v_{sat}(V_{DD}-V_T-V_{SAT}/2)$
- $R_{eq}: V_{DD}/I_{DSAT}$

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27

## *Full Scaling (Dennard, Short-Channel)*

- $W, L, t_{ox}: 1/S$
- $V_{DD}, V_T: 1/S$
- $t_p: R_{eq}C_L$
- $P_{avg}: C_L V_{DD}^2/t_p$
- $P_{avg}/A: C_{ox} V_{DD}^2/t_p$

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28

## Transistor Scaling (Velocity-Saturated Devices)

Parameter	Relation	Full Scaling	General Scaling	Fixed-Voltage Scaling
$W, L, t_{ox}$		$1/S$	$1/S$	$1/S$
$V_{DD}, V_T$		$1/S$	$1/U$	1
$N_{SUB}$	$V/W_{dop}^2$	$S$	$S^2/U$	$S^2$
Area/Device	$WL$	$1/S^2$	$1/S^2$	$1/S^2$
$C_{ox}$	$1/t_{ox}$	$S$	$S$	$S$
$C_{gate}$	$C_{ox}WL$	$1/S$	$1/S$	$1/S$
$k_n, k_p$	$C_{ox}W/L$	$S$	$S$	$S$
$I_{sat}$	$C_{ox}WV$	$1/S$	$1/U$	1
Current Density	$I_{sat}/Area$	$S$	$S^2/U$	$S^2$
$R_{on}$	$V/I_{sat}$	1	1	1
Intrinsic Delay	$R_{on}C_{gate}$	$1/S$	$1/S$	$1/S$
$P$	$I_{sat}V$	$1/S^2$	$1/U^2$	1
Power Density	$P/Area$	1	$S^2/U^2$	$S^2$

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29

## An interesting question

- ❑ What ~~will~~ did cause this model to break?
  - Leakage set by  $kT/q$ 
    - Temp. does not scale
    - $V_T$  set to minimize power
  - Power actually increased
    - Leakage increased drastically
    - $f$  increased faster than device speed
    - Hit cooling limit
  - Process Variation
    - Hard to build very small things accurately (less averaging)

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30